



NOTES

1. COATING (S1) : LOW GDD COATING
 $R_s > 99\% @ 460 \text{ nm} - 590 \text{ nm}, \text{AOI} = 45^\circ$
 $R_p > 99\% @ 480 \text{ nm} - 560 \text{ nm}, \text{AOI} = 45^\circ$
2. GDD:
 $|GDD_s| < 30 \text{ fs}^2 @ 460 \text{ nm} - 590 \text{ nm}, \text{AOI} = 45^\circ$
 $|GDD_p| < 30 \text{ fs}^2 @ 480 \text{ nm} - 560 \text{ nm}, \text{AOI} = 45^\circ$
3. CLEAR APERTURE (S1, S2) : $> 90\% \text{CA}$
4. SURFACE QUALITY (S1, S2) : 20/10(S/D)
5. SURFACE FLATNESS (S1) : $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) : $< 10 \text{ arcsec}$
7. CHAMFER: 0.1 mm, 45°
8. THICKNESS TOLERANCE: $\pm 0.1 \text{ mm}$
9. DIAMETER TOLERANCE: $+0.0 \text{ mm} / -0.1 \text{ mm}$
10. OTHER SURFACES: FINE GROUND

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	LZHOU	Aug./5th/24	ULTRAFAST MIRROR $\text{Ø} 50.8 \text{ mm} \times 12 \text{ mm}, 460 \text{ nm} - 590 \text{ nm}$			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	26.5 g	1:1	B